

Form PTO 1449
(Modified)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO.

236518US26YA

SERIAL NO.

10/673,138

LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Andrej S. MITROVIC

FILING DATE

September 30, 2003

GROUP

2128

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
/A.S./	AA	US 6,571,371	5/2003	Coss, et al.			
	AB	US 6,763,277	7/2004	Allen, et al.			
	AC	US 6,529,789	3/2003	Campbell, et al.			
	AD	US 6,628,809	9/2003	Rowe, et al.			
	AE	US 6,728,591	4/2004	Hussey, et al.			
	AF	US 6,774,998	8/2004	Wright, et al.			
	AG	US 2005/0010319	1/2005	Patel, et al.			
	AH	US 2004/0044513	3/2004	Kitahara, Noriaki			
	AI	US 6,615,097	9/2003	Ozaki, Hiroji			
/A.S./	AJ	US 6,618,856	9/2003	Coburn, et al.			Repeated.
	AK	US 2004/0044513	3/2004	Kitahara, Noriaki			
/A.S./	AL	US 5,539,652	7/23/1996	Tegethoff			
	AM	US 6,581,029 B1	6/17/2003	Fisher			
/A.S./	AN	US 2003/0003607	1/2/2003	Kagoshima et al			

FOREIGN PATENT DOCUMENTS

Not provided.

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	AQ	CN 1335558A	2/13/2002	China (with Partial English Translation)	X	
/A.S./	AP	JP 2004-527117	9/2/2004	Japan		X
/A.S./	AQ	WO 03/060779 A1	7/24/2003	WIPO		X
/A.S./	AR	JP 2005-515623	5/26/2005	JAPAN (With English Abstract)		X
/A.S./	AS	WO 03/009345 A2	1/30/2003	WIPO		X
/A.S./	AT	JP 2005-522018	7/21/2005	JAPAN (With English Abstract)		X
/A.S./	AU	JP 2002-367875	12/20/2002	JAPAN		X
/A.S./	AV	JP 2003-502771	1/21/2003	JAPAN		X

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

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	AW	Robert W. ATHERTON, et al., "Detailed Simulation for Semiconductor Manufacturing", Proceedings of the 1990 Winter Simulation Conference	
	AX	Angus J. MACDONALD, et al, "Integrated CAM and Process Simulation to Enhance On-Line Analysis and Control of IC Fabrication"; IEEE Transactions on Semiconductor Mfg., Vol. 3, No. 2, May 1990	
	AY	Yea-Huey SU, et al. "Conceptual Framework for Manufacturing Service Provisioning by Virtual Fabs"; 1998 NSC Republic Of China; 1998 Semiconductor Mfg. Technology Workshop	
	AZ	Chanette RAS MIDATTA, et al. "New approaches for Simulation of Wafer fabrication : The Use of Control Variates and Calibration Metrics" Proceedings of 2002 Winter Simulation Conference; 2002	<input type="checkbox"/> Additional References sheet(s) attached

Examiner /Akash Saxena/ (12/14/2010)

Date Considered 12/14/2010

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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/A.S./	AAA	US 5,377,116	12/1994	Wayne, et al.			
↓	AAB	US 5,629,877	5/1997	Tamegaya, Yukio			
	AAC	US 6,625,497	9/2003	Fairbairn, et al.			
	AAD	US 6,185,472	2/6/2001	Onga, et al.			
/A.S./	AAE						
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		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION		
					YES	NO	
/A.S./	AAO	JP 2003-17471	1/17/2003	JAPAN (With English Abstract)			X
/A.S./	AAP	WO 02/065511 A2	8/22/2002	WIPO			X
/A.S./	AAQ	JP 2004-524685	8/12/2004	JAPAN			X
/A.S./	AAR	WO 02/069063 A2	9/6/2002	WIPO			X
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	AAT						
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	AAX	Naomi YONEMURA, et al. "Heat Analysis on Insulated Metal Substrates", 1996, IEEE, pgs. 1407-1410					
	AAY	Tony C. MIDEA, et al., "Casting Simulation Software Survey", 1999, pages 1-4					
/A.S./	AAZ	Heru SETYAWAN, et al. "Visualization and numerical simulation of fine particle transport in a low-pressure parallel plate chemical vapor deposition reactor", Chemical Engineering Science 57 (2002) pages 497-506					
						<input type="checkbox"/> Additional References sheet(s) attached	
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EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
/A.S./	AAAA	US 7,047,095 B2	5/16/2006	Tomoyasu			
/A.S./	AAAB	US 6,587,744 B1	7/1/2003	Stoddard, et al.			
	AAAC						
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/A.S./	AAAO	JP 2000-517473	12/26/2000	JAPAN (With English Abstract)			X
/A.S./	AAAP	WO 03/058699 A1	7/17/2003	WIPO			X
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	AAAS						
	AAAT						
	AAAU						
	AAAV						
	AAAW						
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